CLAIMS

1. A urethane resin obtained by polymerizing a polymerizable composition, which comprises (A) a polyrotaxane having a composite molecular structure comprising an axial molecule and a plurality of cyclic molecules clathrating the axial molecule, wherein side chains having a group with active hydrogen which are introduced into at least some of the cyclic molecules, and (B) a polyiso(thio)cyanate compound, wherein the polyiso(thio)cyanate compound (B) contains (B2) a urethane prepolymer having an iso(thio)cyanate group at the end of the molecule which is obtained by reacting (C1) a bifunctional active hydrogen-containing compound having two groups with active hydrogen in the molecule with (B1) a bifunctional iso(thio)cyanate group-containing compound having two iso(thio)cyanate groups in the molecule.

2. The urethane resin according to claim 1, wherein the polymerizable composition comprises 3 to 2,000 parts by mass of the polyiso(thio)cyanate compound (B) based on 100 parts by mass of the polyrotaxane (A).

3. The urethane resin according to claim 1, wherein the polymerizable composition further comprises (C) an active hydrogen-containing compound having a group with active hydrogen except for the polyrotaxane (A).

4. The urethane resin according to claim 3, wherein the active hydrogen-containing compound (C) contains an amino group compound (CA) having an amino group as the group having active hydrogen.

5. The urethane resin according to claim 3, wherein the polymerizable composition comprises 10 to 3,000 parts by mass of the polyiso(thio)cyanate compound (B) and 3 to 2,000 parts by mass of the active hydrogen-containing compound (C) based

on 100 parts by mass of the polyrotaxane (A).

6. The urethane resin according to claim 1, wherein the isocyanate equivalent of the polyiso(thio)cyanate compound (B) containing the urethane prepolymer (B2) is 300 to 5,000.

7. A polishing pad made of the urethane resin of claim 1.

8. The urethane resin according to claim 4, wherein the polymerizable composition comprises 10 to 3,000 parts by mass of the polyiso(thio)cyanate compound (B) and 3 to 2,000 parts by mass of the active hydrogen-containing compound (C) based on 100 parts by mass of the polyrotaxane (A).

9. A polishing pad made of the urethane resin of claim 2.

10. A polishing pad made of the urethane resin of claim 3.

11. A polishing pad made of the urethane resin of claim 4.

12. A polishing pad made of the urethane resin of claim 5.

13. A polishing pad made of the urethane resin of claim 6.